

8th WORKSHOP EUV-FEL

January 29th, 2024

13:00-17:00 JST Hybrid

Akihabara UDX Gallery NEXT-1
<https://udx.jp/en/>

EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK



JST (UTC + 9)
Japan Time

Opening

13:00-13:10	Opening remarks	Prof. Sunao Ishihara Representative of EUV-FEL Light Source Study Group for Industrialization
13:10-13:15	Greeting	Dr. Tetsuyuki Muramatsu MEXT
13:15-13:25	Target of the workshop	Prof. Hiroshi Kawata KEK (Secretary of the Workshop)

Keynote Lecture

13:25-14:05	The Future of Semiconductor Manufacturing: New Developments in Speed and Innovation.	Dr. Kazunari Ishimaru Rapidus Corporation
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Invited Talk

14:05-14:35	The Last Light Source	Dr. Erik R. Hosler xLight, Inc.
14:35-15:05	Overview of accelerator element development in KEK for realization of EUV-FEL	Prof. Shinichiro Michizono Accelerator Laboratory, KEK
15:05-15:20	Break	
15:20-15:50	The importance of and methods for coherence reduction in accelerator based lithography systems	Dr. Patrick P. Naulleau EUV Tech Inc., Lawrence Berkeley National Laboratory
15:50-16:20	The current status and difficulties in manufacturing multilayer mirrors for BEUV lithography	Dr. Hisataka Takenaka TOYAMA Co., Ltd.
16:20-16:50	Plasma Dynamics and Future of LPP-EUV Source for Semiconductor Manufacturing	Prof. Hakaru Mizoguchi et al. Quantum and Photonics Technology Research Center, Kyushu University

Closing address & Photo-session

16:50-17:00	Closing address	Koki Uchimaru KEK, Executive Director
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